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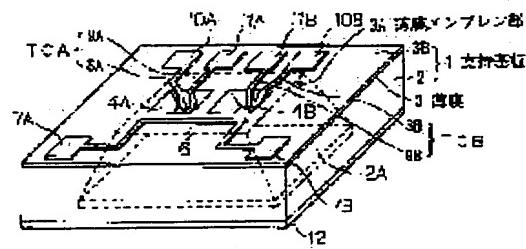
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(54) THERMAL ANALYSIS ELEMENT AND ITS MANUFACTURE

(57) Abstract:

PROBLEM TO BE SOLVED: To obtain a thermal analysis element for satisfactorily thermally analyzing a trace amount of sample.

SOLUTION: A frame-like board 2 having a predetermined thickness is covered with a thin film 3, and sample cells 4A, 4B for containing and holding samples are formed in a thin film membrane 3A having a cavity at a bottom of a center of the film 3. A thin film heater 6 for heating the samples in the cells 4A, 4B and thin film thermocouples TCA, TCB for sensing temperature changes upon absorbing or generating of heats of the samples are formed on the membrane 3A. A thermal capacity of the membrane 3A at the center of the film 3 is extremely reduced as compared with that of a peripheral region. Thus, even if trace amounts of samples exist in the cells 4A, 4B, temperature of the membrane 3A changes with satisfactory sensitivity upon absorbing or generating of the heats of the samples, and heat absorbing or generating reaction of the sample can be accurately detected.



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